Evolution of structural and electrical properties of molecular layer deposited hafnicone films after thermal processing for applications in low-*k* etch stops

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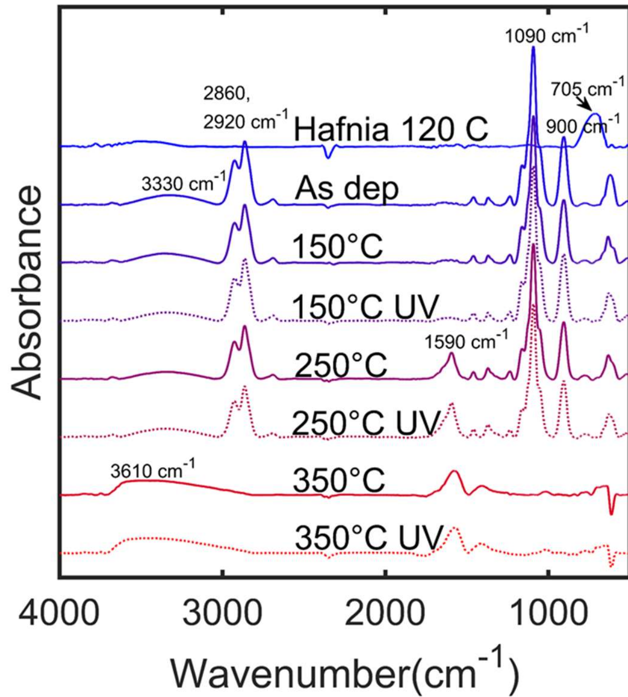

Figure 1: Ex-situ FTIR spectra of as-deposited and thermally processed hafnicone films compared to as-deposited hafnia film

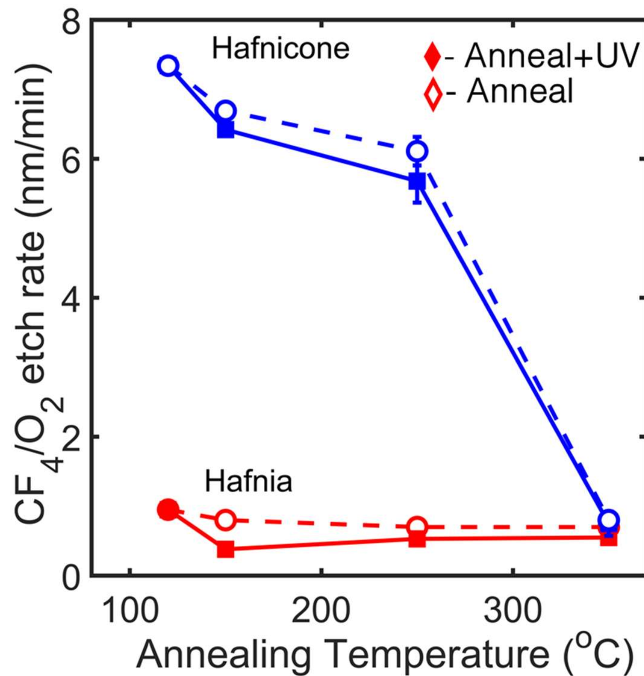

Figure 2: CF_4/O_2 plasma etch rate of as-deposited and thermally processed hafnicone films compared with hafnia

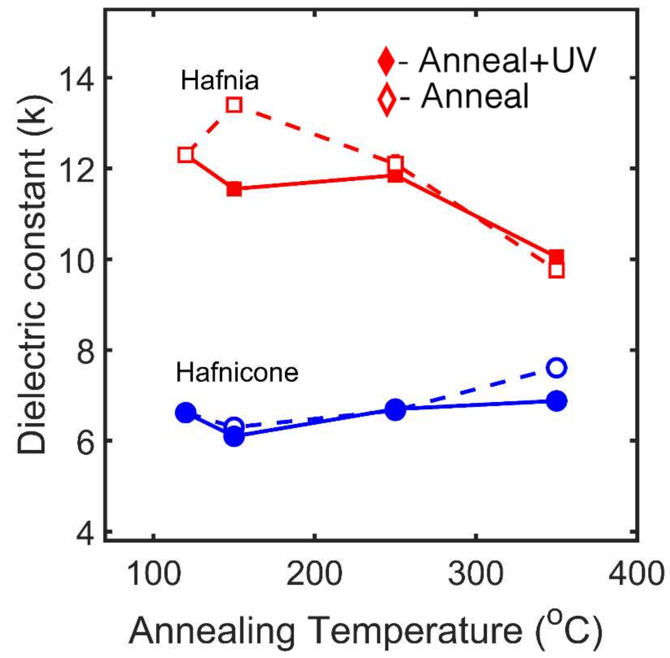

Figure 3: Dielectric constant vs annealing temperature of as-deposited and thermally processed hafnicone films compared to hafnia